



1744

Attorney Docket No.: PATENT  
SSI-08200

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: ) Group Art Unit: 1744  
William Dale Jones ) Examiner:  
Serial No.: 10/630,640 ) **TRANSMITTAL LETTER**  
Filed: July 29, 2003 ) 162 N. Wolfe Road  
Sunnyvale, CA 94086  
For: **REGULATION OF FLOW OF** ) (408) 530-9700  
**PROCESSING CHEMISTRY ONLY** ) Customer No.: 28960  
**INTO A PROCESSING CHAMBER** )

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313

Sir:

Enclosed please find an Information Disclosure Statement and Form PTO-1449, including copies of the references contained thereon, for filing in the U.S. Patent and Trademark Office.

You will also find enclosed the associated Transmittals, Electronic Information Disclosure Statements, and United States Patent and Trademark Office Acknowledgment Receipts for the electronically filed Information Disclosure Statement (EFS ID #53516); (EFS ID #53518); (EFS ID #53520); (EFS ID #53521); (EFS ID #53522); (EFS ID #53523); and (EFS ID #53526) filed on January 12, 2004.

The Commissioner is hereby authorized to charge any additional fee or credit overpayment to our Deposit Account No. 08-1275. **An originally executed duplicate of this transmittal is enclosed for this purpose.**

Respectfully submitted,  
HAVERSTOCK & OWENS LLP

Dated: 1-14-04

By: Thomas B. Haverstock  
Thomas B. Haverstock  
Reg. No.: 32,571

Attorneys for Applicant

CERTIFICATE OF MAILING (37 CFR § 1.8(a))

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HAVERSTOCK & OWENS LLP.

Date: 1-14-04 By: John A. Rosca



PATENT  
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William Dale Jones

Serial No.: 10/630,640

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For: **REGULATION OF FLOW OF  
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) Group Art Unit: 1744

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) **INFORMATION DISCLOSURE  
STATEMENT**

) 162 N. Wolfe Road  
) Sunnyvale, CA 94086  
) (408) 530-9700

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P.O. Box 1450  
Alexandria, VA 22313

Sir:

The citations listed below, copies attached, may be material to the examination of the above-identified application, and are therefore submitted in compliance with the duty of disclosure defined in 37 C.F.R. §§ 1.56 and 1.97. The Examiner is requested to make these citations of official record in this application.

United States Patents or Published Patent Applications have been filed electronically (EFS ID #53516); (EFS ID #53518); (EFS ID #53520); (EFS ID #53521); (EFS ID #53522); (EFS ID #53523); and (EFS ID #53526). Applicants have become aware of the following printed publication which may be material to the examination of this application:

- Chinese Publication No. CN 1399790 A;
- German Publication No. DE 36 08 783 A1;
- German Publication No. DE 39 04 514 C2;
- German Publication No. DE 39 06 724 C2;
- German Publication No. DE 39 06 735 C2;
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This Information Disclosure Statement under 37 C.F.R. §§ 1.56 and 1.97 is not to be construed as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that anyone or more of these citations constitutes prior art.

Respectfully submitted,  
HAVERSTOCK & OWENS LLP

Dated: 1-14-04

By: Thomas B. Haverstock  
Thomas B. Haverstock  
Reg. No.: 32,571

Attorneys for Applicant

**CERTIFICATE OF MAILING (37 CFR § 1.8(a))**

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- 9 -

HAVERSTOCK & OWENS LLP.

Date: 1-14-04 By: John D. Rusan

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**INFORMATION DISCLOSURE STATEMENT BY APPLICANT**  
(Use Several Sheets If Necessary)

Applicant: William Dale Jones

Filing Date: July 29, 2003

Group Art Unit: 1744

(37 CFR § 1.995b)

**FOREIGN PATENTS OR PUBLISHED FOREIGN PATENT APPLICATIONS**

	Document Number	Publication Date	Country / Patent Office	Class	Subclass	Translation	
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		Document Number	Publication Date	Country / Patent Office	Class	Subclass	Translation	
							Yes	No
	CS	WO 01/78911 A1	10/25/01	PCT	B08B	3/00		X
	CT	WO 01/85391 A2	11/15/01	PCT	B24B			X
	CU	WO 01/94782 A3	12/13/01	PCT	F04B	43/02		X
	CV	WO 02/09894 A2	02/07/02	PCT	B08B			X
	CW	WO 02/11191 A2	02/07/02	PCT	H01L	21/00		X
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Examiner				Date Considered:				
EXAMINER: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								

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(Modified)U.S. Department of Commerce  
Patent and Trademark Office

Attorney Docket No.: SSI-08200

Serial No.: 10/630,640

**INFORMATION DISCLOSURE STATEMENT BY APPLICANT**  
(Use Several Sheets If Necessary)

Applicant: William Dale Jones

Filing Date: July 29, 2003

Group Art Unit: 1744

(37 CFR § 1.98(h))

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Examiner

Date Considered:

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Group Art Unit: 1744

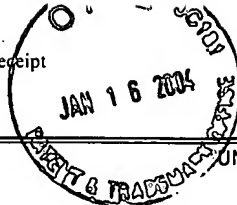
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Electronic Version 1.1

Stylesheet Version v1.1.1

<b>Title of Invention</b>	REGULATION OF FLOW OF PROCESSING CHEMISTRY ONLY INTO A PROCESSING CHAMBER										
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<b>Application Number:</b>	10/630640	*10/630640*									
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<b>Title of Invention</b>	<b>REGULATION OF FLOW OF PROCESSING CHEMISTRY ONLY INTO A PROCESSING CHAMBER</b>						
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Date:	2003-07-29						
First Named Applicant:	William Dale Jones						
Confirmation Number:	8274						
Attorney Docket Number:							
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Thomas B. Haverstock Registered Number: 32571	/tbh/	Attorney					

Documents being submitted	Files
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Comments	

## ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

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Title of  
InventionREGULATION OF FLOW OF PROCESSING CHEMISTRY ONLY INTO A  
PROCESSING CHAMBER

Application Number: 10/630640

\*10/630640\*

Confirmation Number: 8274

First Named Applicant: William Jones

Attorney Docket Number:

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Note: Applicant is not required to submit a paper copy of cited US Patent Documents

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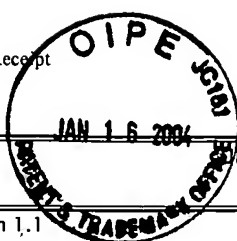
## Remarks

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## Signature

Examiner Name	Date



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<p>I hereby certify that the use of this system is for OFFICIAL correspondence between patent applicants or their representatives and the USPTO. Fraudulent or other use besides the filing of official correspondence by authorized parties is strictly prohibited, and subject to a fine and/or imprisonment under applicable law.</p> <p>I, the undersigned, certify that I have viewed a display of document(s) being electronically submitted to the United States Patent and Trademark Office, using either the USPTO provided style sheet or software, and that this is the document(s) I intend for initiation or further prosecution of a patent application noted in the submission. This document(s) will become part of the official electronic record at the USPTO.</p>							
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Thomas B. Haverstock Registered Number: 32571	/tbh/	Attorney					

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## ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

Title of  
InventionREGULATION OF FLOW OF PROCESSING CHEMISTRY ONLY INTO A  
PROCESSING CHAMBER

Application Number: 10/630640

\*10/630640\*

Confirmation Number: 8274

First Named Applicant: William Jones

Attorney Docket Number:

Search string: ( 5044871 or 5062770 or 5068040 or 5071485 or 5105556 or  
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5285352 or 5288333 or 5290361 or 5294261 or 5298032 ).pn.

## US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

Init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
	1	5044871	1991-09-03	Davis et al.			
	2	5062770	1991-11-05	Story et al.			
	3	5068040	1991-11-26	Jackson			
	4	5071485	1991-12-10	Matthews et al.			
	5	5105556	1992-04-21	Kurokawa et al.			
	6	5143103	1992-09-01	Basso et al.			
	7	5158704	1992-10-27	Fulton et al.			

8	5167716	1992-12-01	Boltnott et al.
9	5169296	1992-12-08	Wilden
10	5169408	1992-12-08	Biggerstaff et al.
11	5174917	1992-12-29	Monzyk
12	5185058	1993-02-09	Cathey, Jr.
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50	5298032	1994-03-29	Schlenker et al.

## Remarks

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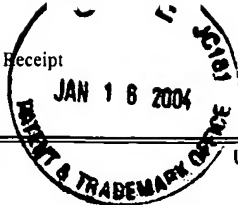
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Date

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ACKNOWLEDGEMENT RECEIPT

Electronic Version 1.1

Stylesheet Version v1.1.1

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Digital Certificate Holder Name: cn=Thomas B. Haverstock,ou=Registered Attorneys,ou=Patent and Trademark Office,ou=Department of Commerce,o=U.S. Government,c=US

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Application Number:	10/630640 *10/630640*						
Date:	2003-07-29						
First Named Applicant:	William Dale Jones						
Confirmation Number:	8274						
Attorney Docket Number:							
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Thomas B. Haverstock Registered Number: 32571	/tbh/	Attorney					

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## ELECTRONIC INFORMATION DISCLOSURE STATEMENT

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Stylesheet Version v18.0

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	1	5304515	1994-04-19	Morita et al.			
	2	5306350	1994-04-26	Hoy et al.			
	3	5312882	1994-05-17	DeSimone et al.			
	4	5313965	1994-05-24	Palen			
	5	5314574	1994-05-24	Takahashi			
	6	5316591	1994-05-31	Chao et al.			
	7	5320742	1994-06-14	Fletcher et al.			

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9	5334332	1994-08-02	Lee
10	5334493	1994-08-02	Fujita et al.
11	5337446	1994-08-16	Smith et al.
12	5339844	1994-08-23	Stanford Jr. et al.
13	5352327	1994-10-04	Witowski
14	5355901	1994-10-18	Mielnik et al.
15	5356538	1994-10-18	Wai et al.
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18	5370740	1994-12-06	Chao et al.
19	5370741	1994-12-06	Bergman
20	5370742	1994-12-06	Mitchell et al.
21	5377705	1995-01-03	Smith, Jr. et al.
22	5401322	1995-03-28	Marshall
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26	5412958	1995-05-09	iliff et al.
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41	5514220	1996-05-07	Wetmore et al.
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46	5550211	1996-08-27	DeCrosta et al.
47	5571330	1996-11-05	Kyogoku
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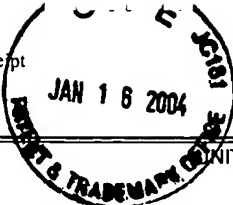
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Non US Patent and Publication references shall be filed under a separate paper transmittal.  
The current electronic filing contains part 3 out of a total of 7 electronic filings.

Signature

Examiner Name	Date




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Stylesheet Version v1.1.1

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	2	5621982	1997-04-22	Yamashita et al.			
	3	5629918	1997-05-13	Ho et al.			
	4	5632847	1997-05-27	Ohno et al.			
	5	5635463	1997-06-03	Muraoka			
	6	5637151	1997-06-10	Schulz			
	7	5641887	1997-06-24	Beckman et al.			

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43	5881577	1999-03-16	Sauer et al.
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49	5900107	1999-05-04	Murphy et al.
50	5900354	1999-05-04	Batchelder

Remarks

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Acknowledgement Receipt

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<b>Title of Invention</b>	<b>REGULATION OF FLOW OF PROCESSING CHEMISTRY ONLY INTO A PROCESSING CHAMBER</b>						
Application Number:	10/630640 *10/630640*						
Date:	2003-07-29						
First Named Applicant:	William Dale Jones						
Confirmation Number:	8274						
Attorney Docket Number:							
<p>I hereby certify that the use of this system is for OFFICIAL correspondence between patent applicants or their representatives and the USPTO. Fraudulent or other use besides the filing of official correspondence by authorized parties is strictly prohibited, and subject to a fine and/or imprisonment under applicable law.</p> <p>I, the undersigned, certify that I have viewed a display of document(s) being electronically submitted to the United States Patent and Trademark Office, using either the USPTO provided style sheet or software, and that this is the document(s) I intend for initiation or further prosecution of a patent application noted in the submission. This document(s) will become part of the official electronic record at the USPTO.</p>							
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First Named Applicant:	William Jones						
Attorney Docket Number:							
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Note: Applicant is not required to submit a paper copy of cited US Patent Documents							
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	4	5932100	1999-08-03	Yager et al.			
	5	5934856	1999-08-10	Asakawa et al.			
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16	5994696	1999-11-30	Tai et al.
17	6001133	1999-12-14	DeYoung et al.
18	6005226	1999-12-21	Aschner et al.
19	6017820	2000-01-25	Ting et al.
20	6024801	2000-02-15	Wallace et al.
21	6029371	2000-02-29	Kamikawa et al.
22	6035871	2000-03-14	Eul-Yeol
23	6037277	2000-03-14	Masakara et al.
24	6053348	2000-04-25	Morch
25	6056008	2000-05-02	Adams et al.
26	6063714	2000-05-16	Smith et al.
27	6067728	2000-05-30	Farmer et al.
28	6077053	2000-06-20	Fujikawa et al.
29	6077321	2000-06-20	Adachi et al.
30	6082150	2000-07-04	Stucker
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	43	6171645	2001-01-09	Smith et al.			B1
	44	6186722	2001-02-13	Shirai			B1
	45	6200943	2001-03-13	Romack et al.			B1
	46	6203582	2001-03-20	Berner et al.			B1
	47	6216364	2001-04-17	Tanaka et al.			B1
	48	6224774	2001-05-01	DeSimone et al.			B1
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Remarks

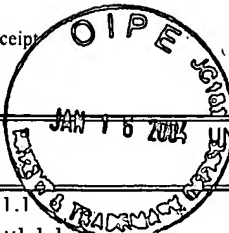
Note: Remarks are not for responding to an office action.

Non US Patent and Publication references shall be filed under a separate paper transmittal.  
The current electronic filing contains part 5 out of a total of 7 electronic filings.

Signature

Examiner Name	Date

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	<b>UNITED STATES PATENT AND TRADEMARK OFFICE</b> <b>ACKNOWLEDGEMENT RECEIPT</b>
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Electronic Version 1.1

Stylesheet Version v1.1.1

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<b>Title of Invention</b>	REGULATION OF FLOW OF PROCESSING CHEMISTRY ONLY INTO A PROCESSING CHAMBER						
Application Number:	10/630640 *10/630640*						
Date:	2003-07-29						
First Named Applicant:	William Dale Jones						
Confirmation Number:	8274						
Attorney Docket Number:							
<p>I hereby certify that the use of this system is for OFFICIAL correspondence between patent applicants or their representatives and the USPTO. Fraudulent or other use besides the filing of official correspondence by authorized parties is strictly prohibited, and subject to a fine and/or imprisonment under applicable law.</p> <p>I, the undersigned, certify that I have viewed a display of document(s) being electronically submitted to the United States Patent and Trademark Office, using either the USPTO provided style sheet or software, and that this is the document(s) I intend for initiation or further prosecution of a patent application noted in the submission. This document(s) will become part of the official electronic record at the USPTO.</p>							
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Title of  
Invention

REGULATION OF FLOW OF PROCESSING CHEMISTRY ONLY INTO A  
PROCESSING CHAMBER

Application Number: 10/630640 \*10/630640\*  
Confirmation Number: 8274  
First Named Applicant: William Jones  
Attorney Docket Number:  
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## US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

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	1	6232238	2001-05-15	Chang et al.	B1		
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49	6562146	2003-05-13	DeYoung et al.	B1
50	6564826	2003-05-20	Shen	B1

## Remarks


Note: Remarks are not for responding to an office action.

Non US Patent and Publication references shall be filed under a separate paper transmittal.  
The current electronic filing contains part 6 out of a total of 7 electronic filings.

## Signature

Examiner Name

Date

	UNITED STATES PATENT AND TRADEMARK OFFICE ACKNOWLEDGEMENT RECEIPT
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Electronic Version  
 Stylesheet Version VI

Title of Invention	REGULATION OF FLOW OF PROCESSING CHEMISTRY ONLY INTO A PROCESSING CHAMBER										
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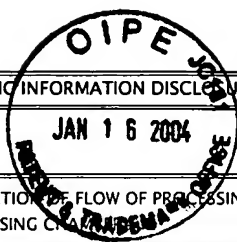
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Application Number:	10/630640 *10/630640*						
Date:	2003-07-29						
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<p>I hereby certify that the use of this system is for OFFICIAL correspondence between patent applicants or their representatives and the USPTO. Fraudulent or other use besides the filing of official correspondence by authorized parties is strictly prohibited, and subject to a fine and/or imprisonment under applicable law.</p> <p>I, the undersigned, certify that I have viewed a display of document(s) being electronically submitted to the United States Patent and Trademark Office, using either the USPTO provided style sheet or software, and that this is the document(s) I intend for initiation or further prosecution of a patent application noted in the submission. This document(s) will become part of the official electronic record at the USPTO.</p>							
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Submitted by:	Elec. Sign.	Sign. Capacity					
Thomas B. Haverstock Registered Number: 32571	/tbh/	Attorney					

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Electronic Version v18  
Stylesheet Version v18.0

Title of Invention	REGULATION OF FLOW OF PROCESSING CHEMISTRY ONLY INTO A PROCESSING CHAIN
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Application Number: 10/630640 \*10/630640\*

Confirmation Number: 8274

First Named Applicant: William Jones

Attorney Docket Number:

Search string: ( 5672204 or 5817178 or 6508259 or 20010019857 or 20010024247 or 20010041455 or 20010041458 or 20020001929 or 20020055323 or 20020074289 or 20020081533 or 20020088477 or 20020098680 or 20020106867 or 20020112740 or 20020112746 or 20020115022 or 20020117391 or 20020123229 or 20020127844 or 20020132192 or 20020141925 or 20020142595 or 20020150522 or 20030003762 or 20030008238 or 20030008518 or 20030013311 or 20030036023 or 20030047533 ).pn.

## US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

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	1	5672204	1997-09-30	Habuka			
	2	5817178	1998-10-06	Mita et al.			
	3	6508259	2003-01-21	Tseronis et al.	B1		

## US Published Applications

Note: Applicant is not required to submit a paper copy of cited US Published Applications

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Signature

Examiner Name	Date

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1	20010019857	2001-09-06	Yokoyama	A1
2	20010024247	2001-09-27	Nakata	A1
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## Remarks

Note: Remarks are not for responding to an office action.

Non US Patent and Publication references shall be filed under a separate paper transmittal.

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